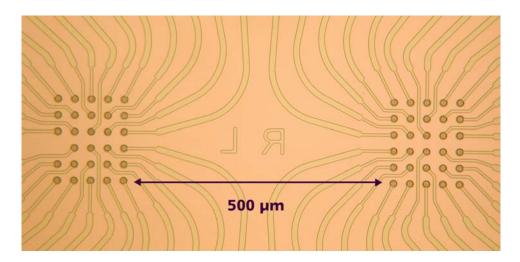
## **HighDenseMEA**

HD30/10iR-ITO



## High Density Microelectrode Array with Internal Reference Electrode



## Technical Specifications: HighDenseMEA

Temperature compartibility Dimension (W x D x H)

Thickness (region of electrodes)

Base material

Contact pads and track material

Electrode diameter

Interelectrode distance (centre to centre)

Distance between electrode fields

Electrode height Electrode type Isolation type

Electrode impedance Electrode layout grid Number of electrodes Reference electrodes

MC Rack:

Source Layout in Data Source Setup

MCS Channel map

MEA perfusion chamber

0 - 125 °C

49 mm x 49 mm x 1 mm

50 µm Glass

Indium tin oxide (ITO)

10 μm 30 μm 500 μm Planar

Titanium nitride (TiN)

Silicone nitride 500 nm (PEVCD) Approximately 250 - 400  $k\Omega$ 

2 x (5 x 6)

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with internal reference electrode

2 dim. (MEA)

HighDenseMEA.cmp HighDenseMEA\_L.cmp HighDenseMEA\_R.cmp

(w/o) Without ring

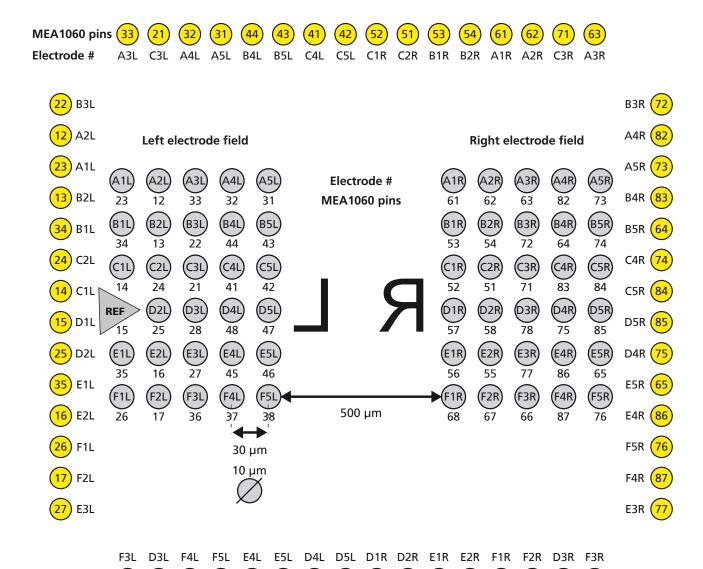
(gr) Glass ring: ID +/- 20 mm, OD 24 mm, height 6 / 12 mm

(pr) Plastic ring without thread: ID 26 mm, OD 30 mm, height 6 / 3 mm (pr-T) Plastic ring with thread: ID 25 mm, OD 30 mm, height 6 / 15 mm

## HighDenseMEA HD30/10iR-ITO



**Electrode Layout** 



The first letter of the electrode number code refers to the row number, the digit is the column number, and the second letter refers to the electrode field (left or right) of the HighDenseMEA. The specified MEA1060 pin numbers are the channel numbers that are used in the MC\_Rack program. The electrode D1 of the left electrode field, connected to channel 15 in MC\_Rack is missing. It is replaced by a big internal reference electrode.

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